

Figure 1. Co EE-ALD nucleation and growth on the native oxide of a silicon wafer.

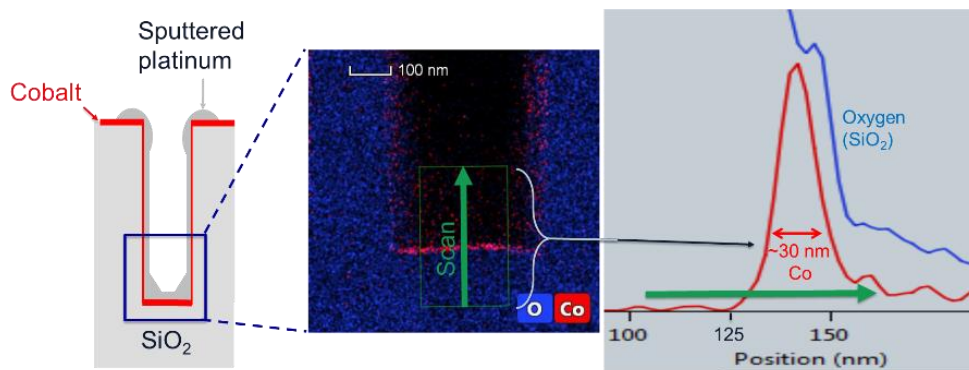


Figure 2. Co EE-ALD cycles on a high aspect ratio via. TEM image reveals a Co film thickness of ~5 nm on the sidewall of the via.

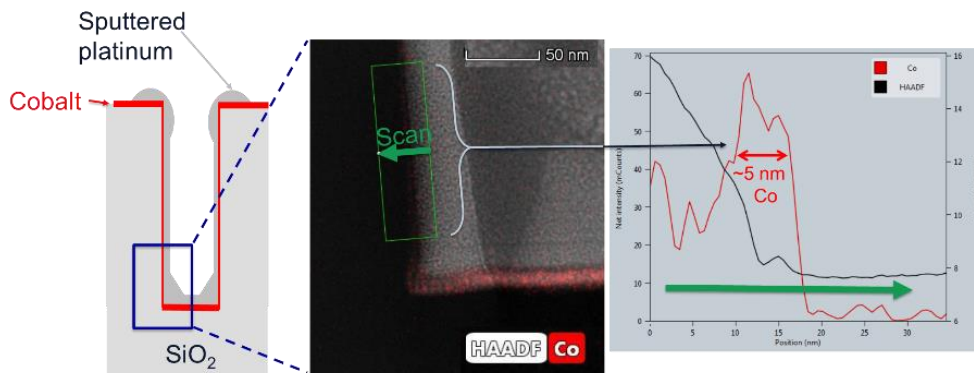


Figure 3. Co EE-ALD cycles on a high aspect ratio via. TEM image reveals a Co film thickness of ~30 nm at the bottom of the via.